

FemtoLux 30

Reliability Redefined

A reliable & versatile tool for micromachining

/ Glass, sapphire and ceramics micro processing

/ Microelectronics manufacturing

/ Glass intra volume structuring

/ Micro processing of different polymers and metals

/ LCD, LED, OLED drilling, cutting and repair

Zero maintenance

EKSPLA

2 years of total warranty

30 W Femtosecond Industrial Laser

FemtoLux 30

Designed from the get-go for maximum reliability, seamless integration and non-stop 24/7/365 zero maintenance operation with innovative "dry" cooling.

The FemtoLux 30 femtosecond laser has a tunable pulse duration from <350 fs to 1 ps and can operate in a broad AOM controlled range of pulse repetition rates from a single shot to 4 MHz.

The maximum pulse energy is more than 100 μJ operating with single pulses and can reach more than 450 μJ in burst mode, ensuring higher ablation rates and processing throughput for different materials.

The FemtoLux 30 beam parameters will meet the requirements of the most demanding materials and micro-machining applications.

Innovative laser control electronics ensure simple control of the FemtoLux 30 laser by external controllers that could run on different platforms, be it Windows, Linux or others using REST API commands.

This makes easy integration and reduces the time and human resources required to integrate this laser into any laser micromachining equipment.

Seamless User Experience

Easy integration - remote control using REST API via RS232 and LAN.

Reduced integration time – demo electronics is available for laser control programming in advance.

Easy and quick installation – no water, fully disconnectable laser head. Can be installed by the end-user.

Easy troubleshooting – integrated detectors and constant system status logging.

No periodic maintenance required.

At 1030 nm

At 515 nm 11 W At 343 nm

Features

Typical max output power 30 W at 1030 nm, 11 W at 515 nm, 6 W at 343 nm

Typical max output energies > 100 μJ at 1030 nm, > 55 μJ at 515 nm, > 30 μJ at 343 nm

High energy version available (**1 mJ** at 10 kHz)

MHz, GHz, MHz+GHz burst modes

> 450 µJ in a burst mode

< 350 fs – 1 ps

Single shot to 4 MHz (AOM controlled)

Pulse-on-demand (PoD), with jitter as low as 20 ns (peak-to-peak)

<0.5% RMS power long term stability over 100 hours

 $M^2 < 1.2$

Beam circularity > 0.85

Zero maintenance

Dry cooling (no water used)

2 years of total warranty



Learn more about FemtoLux 30 www.ekspla.com

*EKSPLA

"Dry" Cooling Direct Refrigerant Cooling System

The FemtoLux 30 laser employs an innovative cooling system and sets new reliability standards among industrial femtosecond lasers. No additional bulky and heavy water chiller is needed.

The chiller requires periodic maintenance – cooling system draining and rinsing and water and particle filter replacement. Moreover, water leakage can cause damage to the laser head and other equipment. Instead of using water for transferring heat from a laser head, the FemtoLux 30 laser uses an innovative Direct Refrigerant Cooling method.

The refrigerant agent circulates from a PSU-integrated compressor and condenser, to a cooling plate via armored flexible lines.

The entire cooling circuit is permanently hermetically

sealed and requires no maintenance.



See **FemtoLux 30** introduction video showing "dry cooling" advantages



Military-grade reliability

Permanently hermetically sealed system >90,000 hour MTBF

No maintenance

High cooling efficiency

>45% lower power consumption compared to water cooling equipment

Compact and light





Simple & Reliable Cooling Plate Attachment

The cooling plate is detachable from the laser head for more convenient laser installation. The laser cooling equipment is integrated with the laser power supply unit into a single 4U rack-mounted housing with a total weight of 15 kg.





Simple and reliable cooling plate attachment

Detachable cooling plate

Integrated cooling equipment with the laser power supply

FemtoLux 30

Specifications ¹⁾

Model		FemtoLux 30
Main specifications		
	fundamental	1030 nm
Central wavelength	with second harmonic option	515 nm
	with third harmonic option	343 nm
Pulse repetition rate (PRR) ²⁾		200 kHz – 4 MHz
Pulse repetition frequency (PRF) after frequency divider		PRF = PRR / N, N=1, 2, 3, , 65000; single shot
Average output power	at 1030 nm	> 27 W (typical 30 W)
	at 515 nm	> 11 W ³)
	at 343 nm	> 6 W ³⁾
Pulse energy	at 1030 nm	> 100 μJ or 1 mJ ⁴⁾
	at 515 nm	> 55 μJ ³⁾
	at 343 nm	> 30 µJ ³⁾
Number of pulses in MHz burst ⁵⁾		2 – 10
Total energy in burst mode		> 450 µJ ⁶⁾
Power long term stability (Std. dev.) 7)		< 0.5 %
Pulse energy stability (Std. dev.) ⁸⁾		< 1 %
Pulse duration (FWHM)		tunable, < 350 fs ⁹⁾ – 1 ps ¹⁰⁾
Beam quality		M ² < 1.2 (typical < 1.1)
Beam circularity, far field		> 0.85
Beam divergence (full angle)		< 1 mrad
Beam pointing thermal stability		< 20 µrad/°C
Beam diameter (1/e ²) at 20 cm distance from laser aperture at 1030 nm		0 nm 2.5 ± 0.4 mm
Triggering mode		internal / external
Pulse output control		frequency divider, pulse picker, burst mode, packet triggering, power attenuation, pulse-on-demand ¹¹⁾
Control interfaces		RS232 / LAN
Length of the umbilical cord		3 m, detachable. Custom length option available
Laser head cooling type		dry (direct refrigerant cooling through detachable cooling plate)
Physical characteristics		
Laser head (W \times L \times H)		429 × 569 × 130 mm
Power supply unit (W \times L \times H)		449 × 376 × 177 mm
Operating requirements		
Mains requirements		100 – 240 V AC, single phase, 50/60 Hz
Maximal power rating		800 W
Operating ambient temperatu	re	18 – 27 °C
Relative humidity		10–80 % (non-condensing)
Air contamination level		ISO 9 (room air) or better
 Due to continuous improvement, all to change without notice. Parameter specifications. They are indications o will vary with each unit we manufact specified for a shortest pulse duratio all specifications are measured at 102 without options. When frequency divider is set to trar controllable by integrated AOM. 	specifications are subject s marked typical are not typical performance and rure. All parameters are n. Unless stated otherwise, 0 nm and for basic system At PR durat smit every pulse. Fully Custo So fr.	U in MHz burst mode or MHz+GHz burst mode KHZ PRR. > 90 µJ energy in GHz burst mode. 20 h after warm-up under constant imental conditions. 2 500 kHz. At PRR < 500 kHz shortest pulse n is < 400 fs. 2 pulse duration by request. For example – fixed arilable.

³⁾ At 200 kHz.

⁴⁾ Other combinations of energy and repetition rate available.

⁵⁾ Oscillator frequency ~50 MHz, ~20 ns separation between pulses.

 $^{11)}\,$ Jitter < 20 ns. Trigger-to-pulse delay < 1 $\mu s.$

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